

Atty Docket No.: 2000-0484B/N1085-90119

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In Re Patent Application of: :
Cheng et al. : **Group Art Unit: 1765**
: **Application No.: 10/649,472** : **Examiner: Chen, Kln Chan**
: **Filing Date: August 27, 2003** :
: **For: Novel Chemical-Mechanical Polishing** : **Date: January 9, 2006**
: **CMP Process for Shallow Trench Isolation** :
:

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Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

AMENDMENT AFTER FINAL

Sir:

This paper is responsive to the Office Action dated September 13, 2005. A petition for a one (1) month extension of time to extend the response due date to January 13, 2005 is included herewith. Kindly enter the following amendments:

Amendments to the Specification begin on page 2 of this paper.

Amendments to the Claims are reflected in the listing of claims which begins on page 3 of this paper.

Remarks begin on page 6 of this paper.